

**Search Notes**

Application/Control No.

10/724,903

Examiner

W. David Coleman

Applicant(s)/Patent under  
Reexamination

SCHWALBE ET AL.

Art Unit

2823

**SEARCHED**

Class	Subclass	Date	Examiner
438	130 233 278	9/7/2005	WDC

**INTERFERENCE SEARCHED**

Class	Subclass	Date	Examiner
438	278	9/7/2005	WDC

**SEARCH NOTES  
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
EAST ver. 2.0.1; USPGPUBS; USPAT; JPO; EPO; Derwent; IBMTDB	9/7/2005	WDC
Applicants form a memory device using a selective etching process utilizing the wordline and photoresist.	9/7/2005	WDC